## In the Claims:

Claim 1-69 (canceled).

Claim 70 (currently amended): An atomic layer deposition apparatus comprising:

a chamber configured to receive substrate for deposition, the chamber having lateral inner walls;

a piezoelectric liner <del>proximate</del> <u>extending substantially parallel to</u> at least a portion of the one of the lateral inner walls, the liner being configured to be lateral of edges of the substrate upon receipt within the chamber; and

at least a pair of acoustic wave drivers associated with on the liner.

Claim 71 (previously presented): The apparatus of claim 70, wherein the acoustic wave driver is adapted to drive the surface acoustic wave in a selected range of frequencies.

Claim 72 (previously presented): The apparatus of claim 71, wherein the selected range of frequencies is chosen from an overall range of about 100Hz to about 200 kHz.

Claim 73 (previously presented): The apparatus of claim 70, wherein the acoustic wave driver comprises at least one transducer.

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Claim 74 (previously presented): The apparatus of claim 70, wherein the piezoelectric liner is cylindrical.

Claim 75 (previously presented): The apparatus of claim 70, wherein the piezoelectric liner is a quartz liner.

Claim 76 (currently amended): The apparatus of claim 70, further comprising a pump coupled to the chamber and operable to evacuate the a first precursor gas from the chamber.

Claim 77 (previously presented): The apparatus of claim 70, wherein the chamber is adapted to receive a second precursor gas.

Claim 78 (previously presented): The apparatus of claim 70, further comprising at least a pair of electrodes associated with at least one of the wave drivers.

Claim 79 (previously presented): The apparatus of claim 78, wherein one of the pair of electrodes is configured to operate at one polarity and the other of the pair of electrodes is configured to operate at another polarity opposite of the one polarity.

Claim 80 (currently amended): The apparatus of claim 70 78, wherein each of the electrodes comprises a conductive backbone having a plurality of conductive prongs extending therefrom.

Claim 81 (previously presented): The apparatus of claim 80, wherein each of the prongs of the electrodes defines a space therebetween and the pair of electrodes are aligned with one another having prongs of one electrode within the space of the other and prongs of the other electrode within the space of the one.

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